

Hafnium Zirconium Oxide Thin Films for CMOS Compatible Pyroelectric Infrared Sensors

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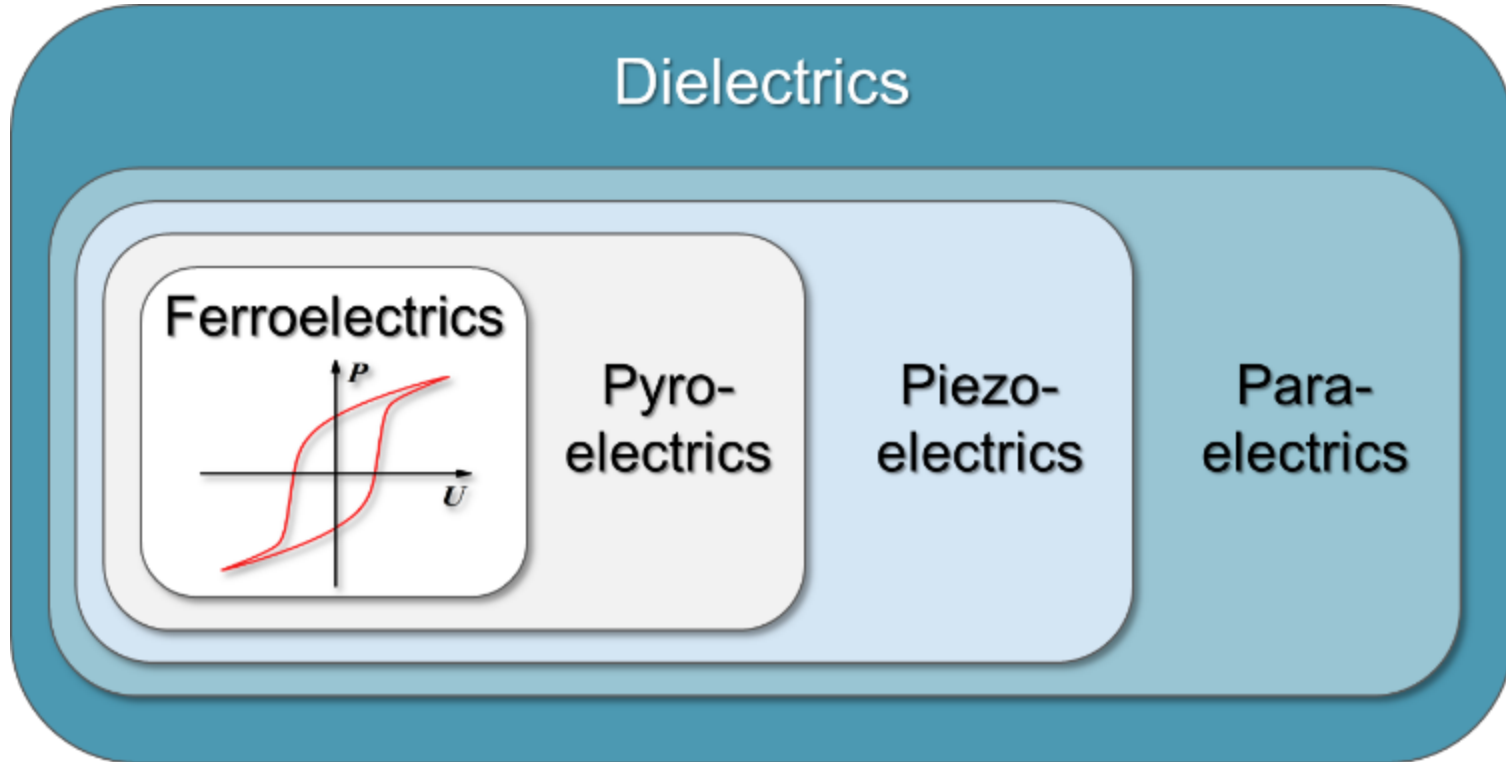
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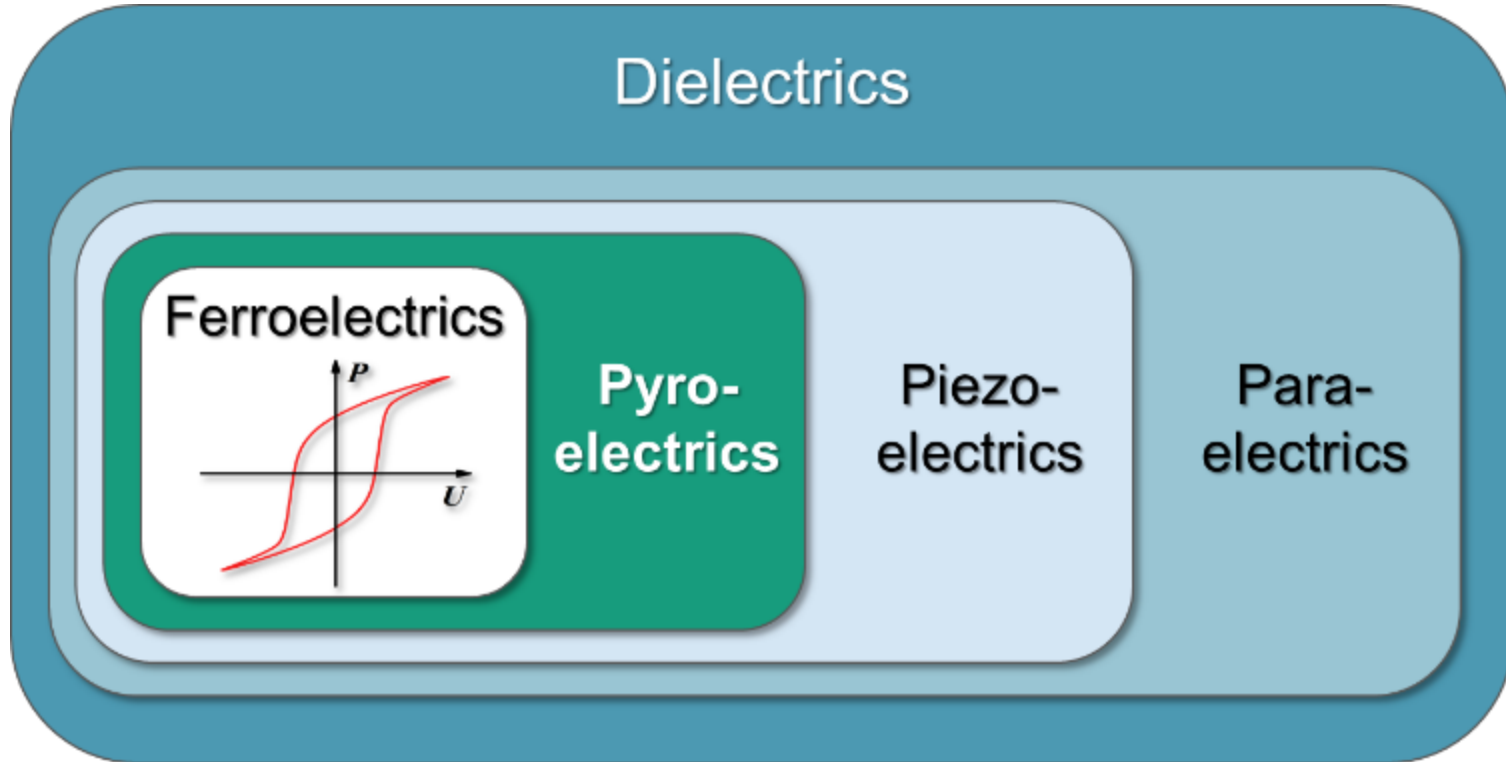
Pyroelectricity

Overview

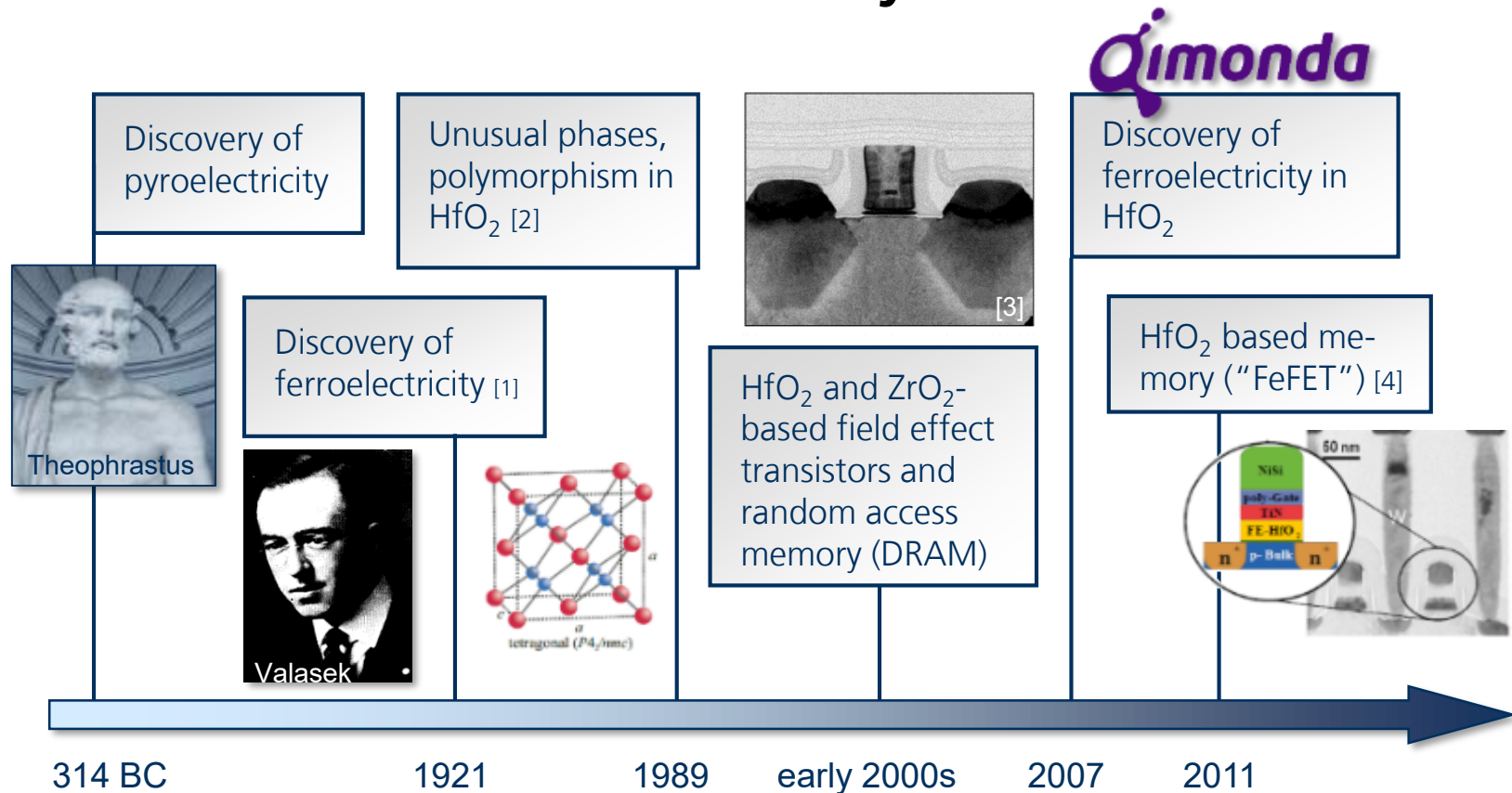


Pyroelectricity

Overview



Doped hafnium oxide: A brief history



[1] J. Valasek Physical Review 17.4 (1921)
[2] E. Kisi et al. J. Am. Ceram. Soc. 72 (1989)

[3] K Mistry et al., IEDM 2007
[4] J. Müller et al., IEDM 2013

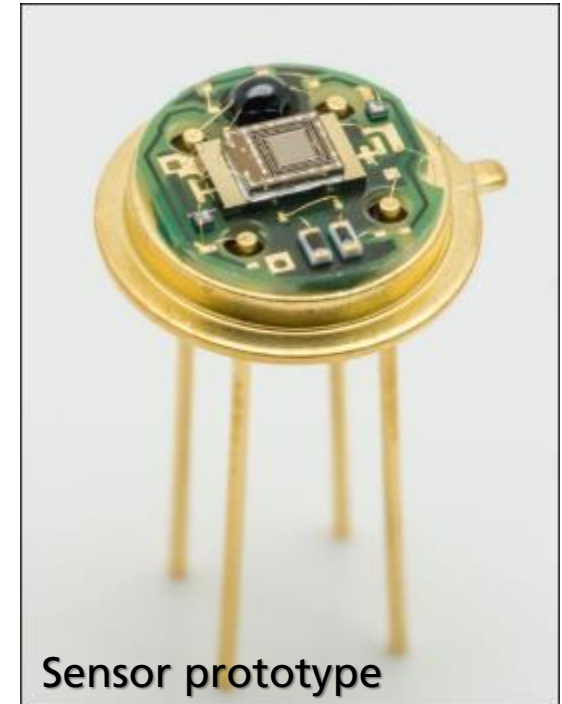
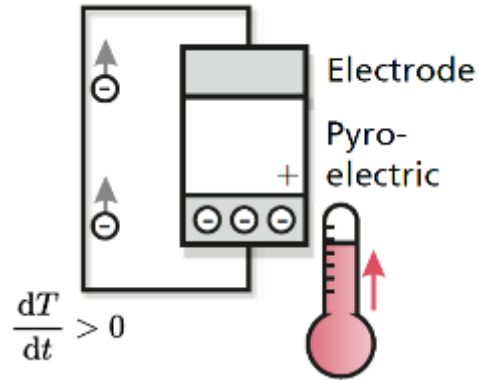
Pyroelectric Infrared Sensors

Working principle

- The pyroelectric effect corresponds to a polarization change upon temperature variation

$$p_i = \underbrace{\frac{\partial P_i}{\partial T}}_{\text{intrinsic}} + \underbrace{E_j \frac{\partial \varepsilon_{ij}}{\partial T}}_{\text{field-induced}}$$

- The effect can be used for infrared detection
- The generated current is proportional to the rate of temperature change



Infrared Sensor development steps

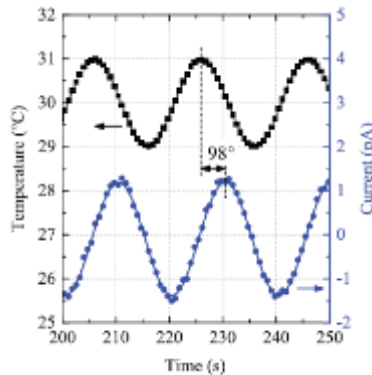
Pyroelectric effect in doped HfO_2

Area-enhanced pyro- HfO_2

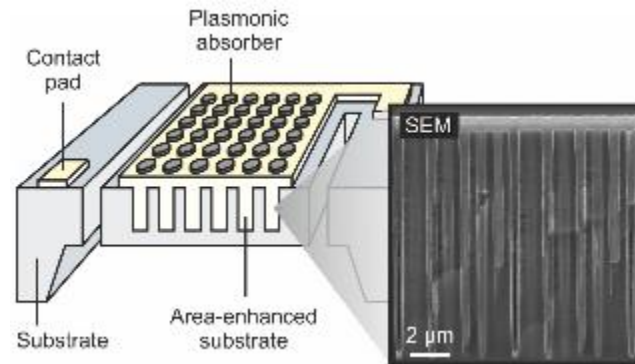
MEMS integration

Infrared Sensor element

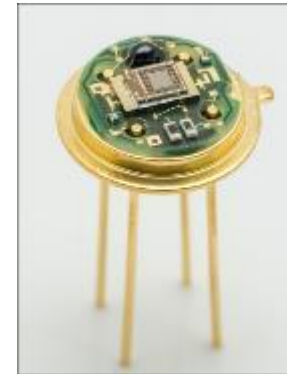
CO_2 Sensor



Mart et al., Appl. Phys. Lett. 112, 052905 (2018)



Mart et al., IFCS ISAF 2019



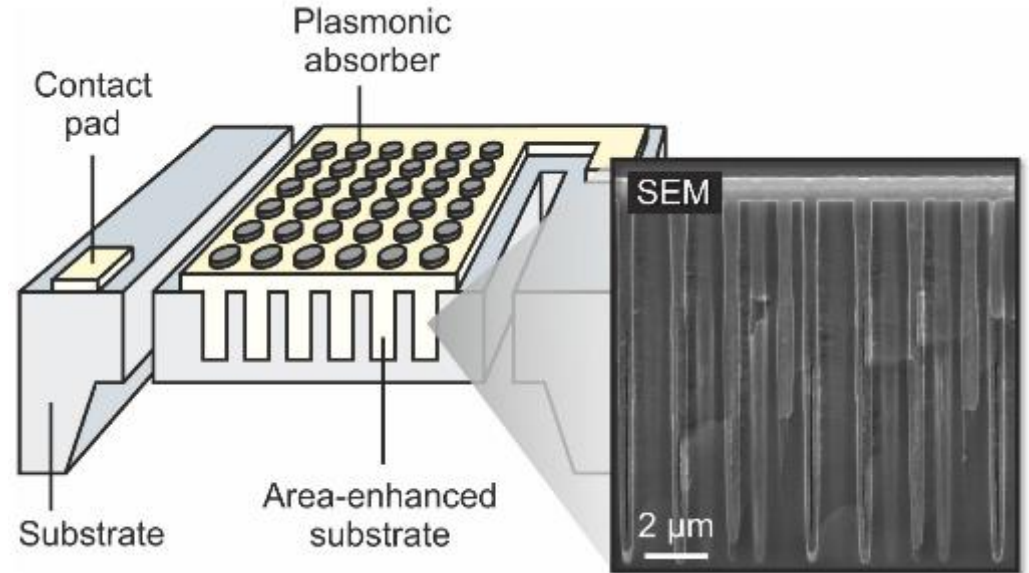
Kindly provided by Infratec GmbH



Pyroelectric sensor technology

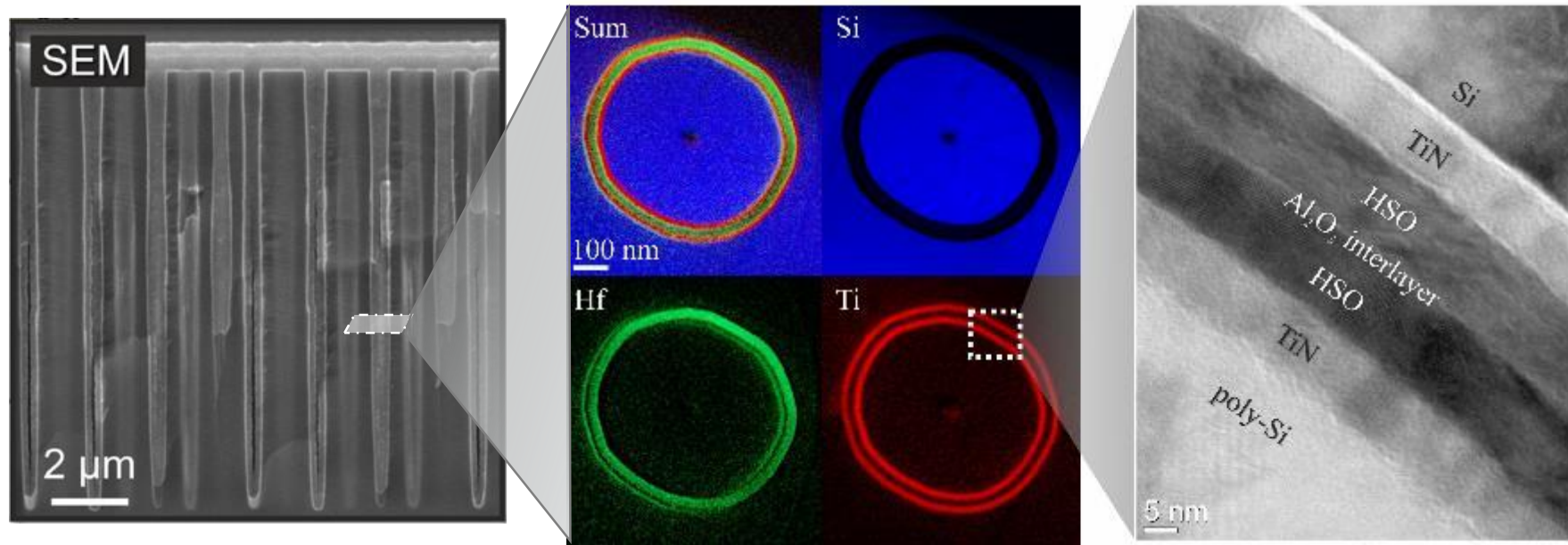
Manufacturing process

- Area-enhanced substrate with 3D structures is used to enhance the pyroelectric response by approx. 20x
- MEMS post-processing forms a thin membrane with reduced heat capacity for fast response
- A further MEMS step isolates the sensor area thermally from the body via “fingers”
- A plasmonic absorber array is formed in the metallization layer
- 300mm technology with i-Line lithography



3D integration of doped HfO₂ thin films

- Pyroelectric material: 20 nm thick, 4 mol% Si-doped HfO₂ with Al₂O₃ interlayer (“nano-laminate”)
- The conformal coating of the 3D structures is confirmed

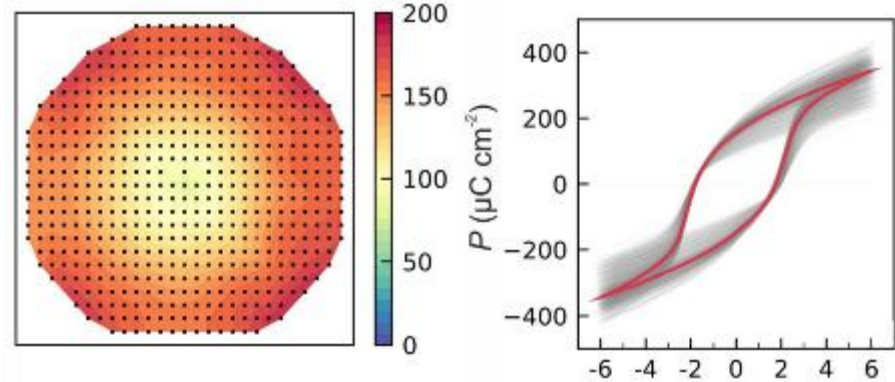


Electrical characterization

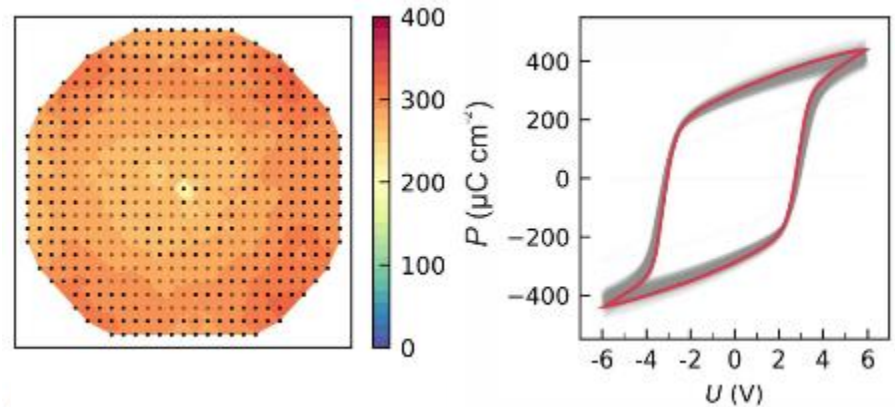
Ferroelectric properties

- Ferroelectric polarization of doped HfO_2 on area-enhanced 300mm substrate with 532 dies.
 - HfZrO_2 exhibits a improved uniformity and larger remanent polarization, up to $331 \mu\text{C cm}^{-2}$
 - Specific area of 11.3 to 15.0 compared to planar results by 3D integration
- Low defect density, >99% functional devices

Si-doped HfO_2 :

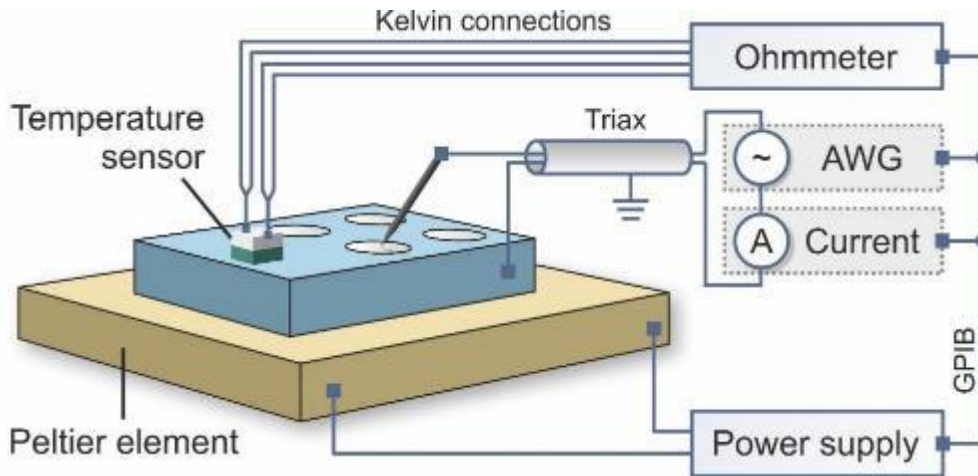
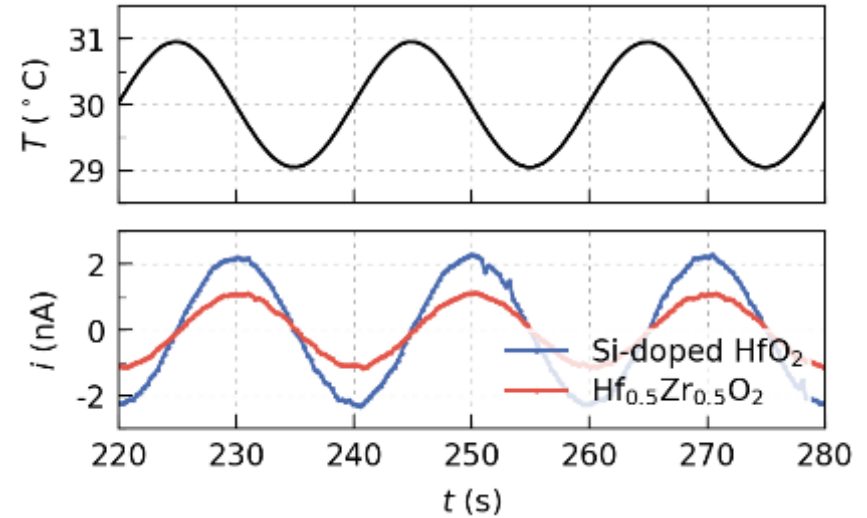


$\text{Hf}_{0.5}\text{Zr}_{0.5}\text{O}_2$:



Pyroelectric characterization

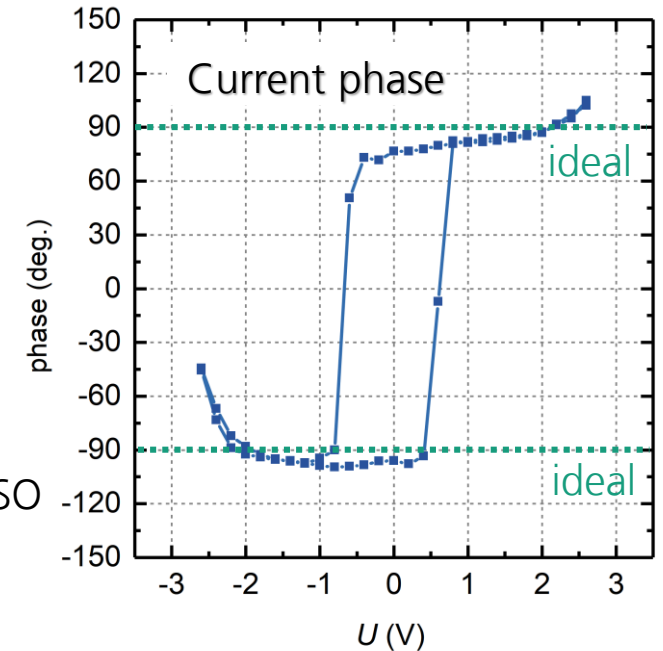
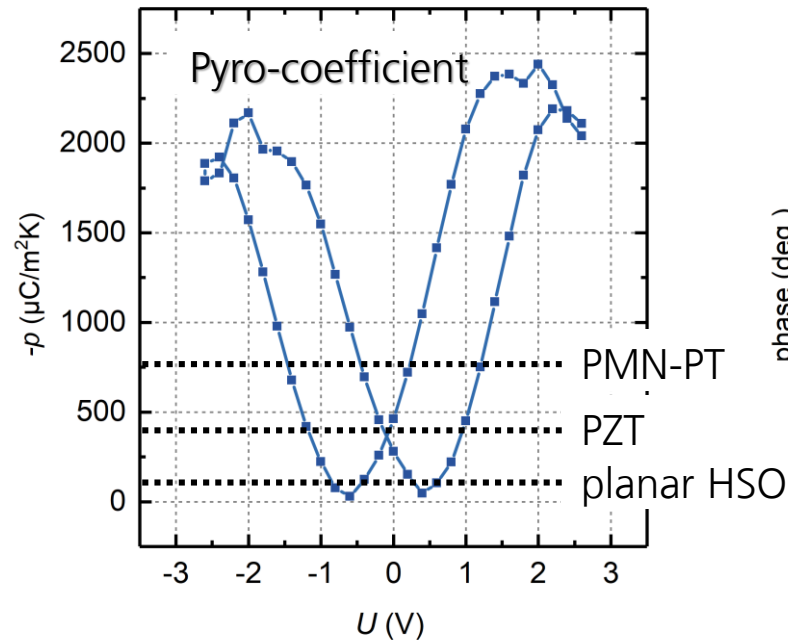
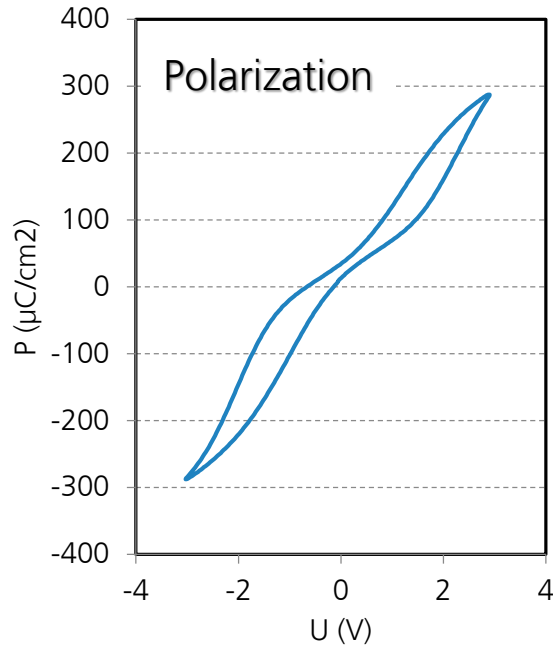
- Pyroelectric measurement is performed by sinusoidal temperature variation ("Sharp-Garn method")
- Although the remanent polarization is smaller, Si-doped HfO_2 realizes larger pyroelectric current amplitudes



	Si-doped HfO_2	$\text{Hf}_{0.5}\text{Zr}_{0.5}\text{O}_2$
Virtual pyroelectric coefficient	$-1039 \mu\text{Cm}^{-2}\text{K}^{-1}$	$-475 \mu\text{Cm}^{-2}\text{K}^{-1}$
Dielectric permittivity	36.9	37.8
Aging coefficient	-5.7 %/dec.	-3.6 %/dec.

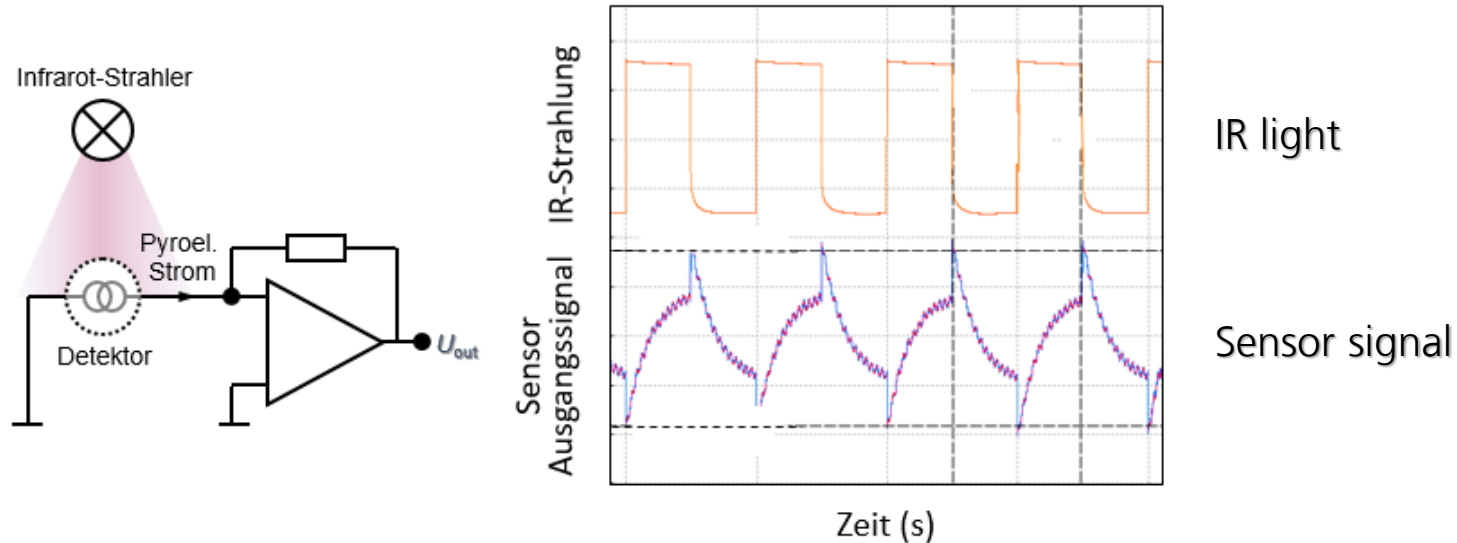
Combining 3D integration and antiferroelectricity

- By tuning the Si doping content higher, antiferroelectric behavior is stabilized
- Very large pyroelectric coefficients by combining area enhancement and AFE enhancement
 - $p = -2400 \mu\text{C}/\text{m}^2\text{K}$



IR Sensor Test

- The sensor current is amplified and converted to a voltage
- The manufactured sensor element produces a signal which is proportional to the amplitude of the incident infrared light



Thank you for listening!

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